

## Why Deep UV Spectroscopy?

Deep UV excited Raman & photoluminescence spectroscopy is an emerging analytical instrument technology with vast potential for a wide range of commercial, industrial, and research applications. A major limitation of Raman spectroscopy conducted in the near UV, visible, or near IR is obscuration or interference of the Raman signals due to background fluorescence from the analyte or its background or surroundings within the laser beam interrogation spot. This interference limits the types of materials and compositions or backgrounds for which Raman spectroscopy is useful.

Autofluorescence is a phenomenon which does not occur below about 270 nm for the vast majority of materials, independent of excitation wavelength. Raman, on the other hand, is dependent on excitation wavelength and when excitation occurs below 250 nm, there exists a spectral region within which to observe over 3000 cm-1 of Raman shifted emissions without obscuration or interference from fluorescence.

This is the driving motivation for spectroscopy conducted in the deep UV with excitation below 250 nm. Also, operation in the deep UV enables simultaneous detection of Raman and fluorescence spectra, enabling the much higher sensitivity of fluorescence and the higher specificity of Raman spectra. There are many other advantages of operation in the deep UV including enhanced Raman signal strength due to resonance effects, simplification of Raman spectra for resonant materials making spectra easier to interpret, small depth of penetration into many materials, which limits interference with background or substrate materials, and other benefits.

Deep UV resonance Raman & photoluminescence spectroscopy has been hampered by the lack of a suitable laser source in the deep UV. Photon Systems has developed a new enabling laser technology to address this problem. These lasers have exceptionally narrow and stable emission linewidths and are hundreds of times smaller, lighter, and lower power consumption that other deep UV lasers. Photon Systems lasers have been vetted in a wide range of harsh commercial, industrial and research applications and have been selected by NASA for the Mars 2020 lander mission for a rover arm mounted deep UV Raman and fluorescence instrument.

The DUV Raman PL 200 is available in three configurations:

H1 Basic Instrument includes a standard XYZ manual translation stage and context camera.

H2 Scan Instrument includes a motorized XY with manual Z stage with mapping function and context camera.

H3 Liquids Instrument includes a cuvette holder for liquids analysis.



## **DUV Raman PL 200**

Fully Integrated, Lab Model Deep UV Resonance Raman & **Photoluminescence** Spectrometer, with microscopic imaging

## **Features**

Excitation Wavelength: 248.6nm.

Polarization: Random (Raman signatures

insensitive to polarization of target materials) Spectrograph: 200 mm Czerny Turner with dual computer controlled 3600ln/mm for Raman & 300 or 600 or 1200 ln/mm for fluorescence. All holographic gratings

**Dispersion:** 2.2 cm<sup>-1</sup>/pixel (w 3600g/mm grating)

Raman Resolution: <25 cm<sup>-1</sup> Entrance Slits: fixed, selectable

**Spectral Spread:**300-3500cm<sup>-1</sup> (3600g/mm

grating)

250nm to 620 nm (300g/mm grating) (1.2 nm res) **Detector:** 3 stage TE Cooled (-35C), back thinned,

back illuminated UV CCD Array. 2048x128

elements, 12x12 micron pixels

Obj. Lens: 5X deep UV achromatic objective

standard.

Context Imaging Camera: 2.4 M pixel (only with

5X objective)

**Image FOV:** 3.1 x 1.74 mm

Sample Stage: 50x50x10mm X-Y-Z manual, std. Motorized Position/Mapping Stage: 50x50 mm X-Y motorized, 10mm Z manual, 2µm resolution,

optional as shown.

**Size & Weight:** 7.0" W x 8.0" H x 24" D, < 25 lb

**Power Consumption:** 

Max power: 100 W Standby: 50 W

Input: 85 VAC to 270 VAC or 24 VDC Safety: Class 3B, DHHS/CDRH, CE, RoHS Environmental: 10° to 35°C, non-condensing **Command & Control**: External laptop or tablet computer via USB for command, control, data processing, chemometrics, data storage, etc.

Patents: U.S. Patents 6,278,869, 7,800,753,

8,395,770, plus pending.